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PATENT ABSTRACTS OF JAPAN

(11)Publication number : 08-082701

(43)Date of publication of application : 26.03.1996

(51)Int.Cl.

G02B 1/11

(21)Application number : 06-218960

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(22)Date of filing : 13.09.1994

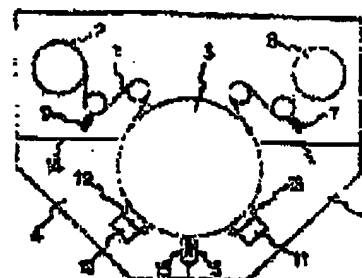
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(54) PRODUCTION OF ANTIREFLECTION FILM

(57)Abstract:

PURPOSE: To easily produce a homogeneous antireflection film by using a plastic film having a black film adhered to the back surface and controlling the formation of the antireflection thin film by measuring the reflectance.

CONSTITUTION: A plastic film 1 with a black film adhered is supplied from a film unwinding machine 2 along a cooling roll 3 to a first sputtering chamber 4 where a first thin film layer is formed. Then the reflectance of the film is measured by a reflectance detector 5. A second thin film layer is formed in a second sputtering chamber and the reflectance of the film is measured by a reflectance detector 7. Then the film is wound on a film winding machine 8. Then, the plastic film is unwound again, a third layer is formed along the cooling roll 3, the reflectance of the film is measured, and wound on the unwinding machine 2. Further, the film is travelled back and forth between the unwinding machine 2 and the winding machine 8 to form fourth and fifth layers. By adhering the black film, very high accuracy of the measurement of reflectance is obt'd. Based on the results of the measurement of reflectance, for example, the deposition amt. of the succeeding film layer is controlled to control the conditions for the formation of films.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's

decision of rejection]

[Date of extinction of right]

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